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APPLICATION NO. FILING DATE		ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO		
09/603,941	09/603,941 06/27/2000		Zhenan Bao	BAO 16-25-12	4437		
. 28221	7590	02/24/2004		EXAM	EXAMINER		
	BOOKS, E TEIN SANI		ECKERT II, GEORGE C				
	SSTON AV		ART UNIT	PAPER NUMBER			
ROSELAN	ND, NJ 070	068	2815				
ROSELAND, NJ 07068				2815			

DATE MAILED: 02/24/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application	on No.	Applicant(s)		m			
		09/603,94		BAO ET AL.		v			
Office Action Summary		Examiner		Art Unit					
		George C.	Eckert II	2815					
	The MAILING DATE of this communication			orrespondence ad	idress				
THE - Exte after - If the - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR F MAILING DATE OF THIS COMMUNICAT nsions of time may be available under the provisions of 37 C SIX (6) MONTHS from the mailing date of this communicate period for reply specified above is less than thirty (30) days of period for reply is specified above, the maximum statutory tre to reply within the set or extended period for reply will, by reply received by the Office later than three months after the ed patent term adjustment. See 37 CFR 1.704(b).	ION. CFR 1.136(a). In no eve ion. 5, a reply within the statu period will apply and will statute, cause the appli	ent, however, may a reply be time story minimum of thirty (30) day Il expire SIX (6) MONTHS from ication to become ABANDONE	nely filed s will be considered timel the mailing date of this c D (35 U.S.C. § 133).					
Status	ed patent term adjustment. See 37 GFR 1.704(b).								
	Decreasive to communication(s) filed on	01 December 20	202						
1)⊠ 2a)⊠	Responsive to communication(s) filed on <u>01 December 2003</u> . This action is FINAL . 2b) This action is non-final.								
3)□	,			secution as to the	e merits is				
<u>ا</u> رن	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disposit	ion of Claims								
5)□ 6)⊠ 7)□	Claim(s) 1-19 is/are pending in the application 4a) Of the above claim(s) 13-18 is/are with Claim(s) is/are allowed. Claim(s) 1-12 and 19 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction is	hdrawn from con							
Applicat	ion Papers								
10)⊠	The specification is objected to by the Example The drawing(s) filed on 25 April 2002 is/an Applicant may not request that any objection Replacement drawing sheet(s) including the of the oath or declaration is objected to by the control of the oath or declaration is objected.	re: a)⊠ accepte to the drawing(s) b correction is require	e held in abeyance. See ed if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 C					
Priority (under 35 U.S.C. § 119								
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 									
2) Notice 3) Infor	at(s) ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-94) mation Disclosure Statement(s) (PTO-1449 or PTO/94) er No(s)/Mail Date		4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:	ate	O-152)				

DETAILED ACTION

Response to Amendment

1. Applicant's response dated December 1, 2003 has been entered of record.

Election/Restrictions

2. Claims 13-18 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim.

Election was made without traverse in Paper No. 6.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-4, 6-12 and 19 are rejected under 35 U.S.C. 102(e) as being anticipated by Hacker (of record). With regard to claims 1, 3, 10, 12 and 19, Hacker teaches, with reference to paragraphs 0001, 0007 and 0083, the formation of transistors comprising a silsesquioxane dielectric layer above a substrate [para. 0007] wherein the silsesquioxane precursor is cured at a temperature of less than about 200° C and less than about 150° C (Hacker teaches in 0083 that the precursor may be cured at 100° C). With regard to claims 2 and 10, Hacker teaches in paragraph 0076 that the silsesquioxane precursor may comprise an alkyl(methyl) group. With regard to claim 4,

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because Hacker teaches the same structure and curing temperature as instantly claimed, it is considered inherent that the high-dielectric strength film will have a will have a dielectric constant greater than 2. With regard to claims 6-9 and 11, these claims are directed to the process by which the product is formed. Note that a "product by process" claim is directed to the product per se, no matter how actually made, In re Hirao, 190 USPO 15 at 17 (footnote 3). See also In re Brown, 173 USPQ 685; In re Luck, 177 USPQ 523; In re Fessmann, 180 USPQ 324; In re Avery, 186 USPQ 161; In re Marosi et al., 218 USPQ 289; and particularly In re Thorpe, 227 USPO 964, all of which make it clear that it is the patentability of the final product per se which must be determined in a "product by process" claim, and not the patentability of the process, and that an old or obvious product produced by a new method is not patentable as a product, whether claimed in "product by process" claims or not. Note that applicant has the burden of proof in such cases, as the above case law makes clear. Instantly, these claims do not structurally differentiate over that taught by Hacker and as such are anticipated.

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Regarding the limitations that a FET is formed on the substrate, Hacker teaches the formation of silsesquioxane to improve the characteristics of integrated circuits which include transistors.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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3. Claim 5 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hacker in view of Fergason et al. Hacker taught the formation of silsesquioxane on a substrate but did not teach that the substrate was an indium-tin-oxide (ITO) coated plastic substrate. Fergason et al teach the use of an ITO coated plastic substrate (col. 9, lines 3-9). Hacker and Fergason et al. are combinable because they are from the same field of endeavor. At the time of the invention it would have been obvious to a person of ordinary skill in the art to use a plastic substrate coated with ITO. The motivation for doing so is that a plastic substrate is more flexible than a conventional glass substrate and less prone to cracking. Therefore, it would have been obvious to combine Hacker with Fergason et al. to obtain the invention of claim 5.

Response to Arguments

4. Applicant's arguments filed December 1, 2003 have been fully considered but they are not persuasive. Applicant first argues that Hacker fails to teach or suggest a FET device or any other semiconductor or transistor device (response, p. 2). However, this argument is against the clear teaching in Hacker, paragraph 0001, which teaches that Hacker's invention is directed toward integrated circuits having thousands or even millions of transistors. Hacker there also teaches the use of thin films of silicon dioxide as dielectric layers. In all, the argument is not persuasive.

Applicant next argues that Hacker's device comprises an alkylated siloxane film rather than a silsesquioxane film (response, pp. 2-3). This argument fails for at least two reasons. First, none of the instant claims cite a limitation as to the composition of the layer after curing. The claims merely cite a liquid deposited silsesquioxane precursor deposited and cured at a specific

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temperature. The argument attempts to define the claim by importing limitations from the specification and is not persuasive. Second, Hacker *does* teach that a silsesquioxane film is formed after curing the precursor. In paragraphs 0081-83, Hacker teaches that the substrate and silsesquioxane precursor is cured "to convert the silsesquioxane molecule composition into a silsesquioxane thin film." In paragraph 0083, Hacker teaches that this cure is done at a low temperature as instantly claimed. As such, Hacker teaches the instant claim limitations and arguments to the contrary are not persuasive.

Conclusion

5. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

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6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to George C. Eckert II whose telephone number is (571) 272-1728. The examiner can normally be reached on 8:00 - 5:30, alternate Fridays off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (571) 272-1664. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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